

### Vacuum Technology

#### RF 3 Cathode Sputtering System (with Plasma Processing Function) (Model: RVS-3N+P)



#### For forming functional thin films!

As three sputtering cathodes are provided, this sputtering system enables independent control of each of the three cathodes. Separately from the sputtering chamber, the system has the plasma processing chamber which can carry out plasma processing prior to and after film forming.

#### Features

1. The target materials can include not only metals but also magnetic materials and insulation materials.
2. Uniform films can be produced through continuous rotation of the sample holder.
3. The material is conveyed from the loading chamber to the film forming chamber and to the plasma processing chamber via the transfer arm, ensuring a continuous film forming work.